

Form PTO-1449 (modified)

Atty. Docket No.
102-0090US-CSerial No.
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List of Patents and Publications for Applicant's

INFORMATION DISCLOSURE STATEMENT

Inventor/Applicant:

Christophe Pierrat et al./ Micron Technology, Inc.

Title: **PROCESS FOR DETECTING
DEFECTS IN PHOTOMASKS**Filing Date:
herewith

Group:

(Use several sheets if necessary)

U.S. Patent Documents

| Exam. Init. | Ref. Des. | Document Number | Date | Name | Class | Sub Class | Filing Date of App. |
|----------------|--------------|--------------------|----------|--------------------------|-------|--------------|------------------------|
| BL | A1 | 4,633,504 | 12-30-86 | Mark J. Wihl | | | 6-28-84 |
| | A2 | 4,926,489 | 5-15-90 | Danielson, et al. | | | 10-05-87 |
| | A3 | 5,563,702 | 10-08-96 | Emery, et al. | | | 7-13-94 |
| | A4 | 5,795,688 | 8-18-98 | Burdorf, et al. | | | 8-14-96 |
| | A5 | 6,064,484 | 5-16-00 | Kobayashi, et al. | | | 3-11-97 |
| | A6 | 4,527,070 | 7-02-85 | Matsui, et al. | | | 8-20-82 |
| | A7 | 5,850,467 | 12-15-98 | Matsui, et al. | | | 11-15-94 |
| | A8 | 5,029,222 | 7-02-91 | Yamada, et al. | | | 8-30-88 |
| | A9 | 4,809,341 | 2-28-89 | Matsui, et al. | | | 7-13-87 |
| | A10 | 5,307,421 | 4-26-94 | Darboux, et al. | | | 10-14-92 |
| | A11 | 5,804,340 | 9-08-98 | Garza, et al. | | | 12-23-96 |
| | A12 | 5,481,624 | 1-02-96 | Kazuya Kamon | | | 4-13-93 |
| | A13 | 5,475,766 | 12-12-95 | Tsuchiya, et al. | | | 9-04-92 |
| | A14 | 5,379,348 | 1-03-95 | Watanabe, et al. | | | 3-31-93 |
| | A15 | 5,048,093 | 9-10-91 | Kimura, et al. | | | 4-11-90 |
| | A16 | 5,306,585 | 4-26-94 | Yoshihiko Okamoto | | | 4-23-93 |
| | A17 | 4,644,172 | 2-17-87 | Sandland, et al. | | | 2-22-84 |
| | A18 | 5,129,009 | 7-07-92 | Christopher J. Lebeau | | | 6-04-90 |
| | A19 | 4,893,346 | 1-09-90 | Robert Bishop | | | 9-02-87 |
| | A20 | 5,707,765 | 1-13-98 | Chen | | | 5-28-96 |
| | A21 | 5,725,974 | 3-10-98 | Kawahira | | | 6-28-96 |
| BL | A22 | 5,441,834 | 8-15-95 | Takekuma | | | 9-10-92 |

EXAMINER:

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DATE CONSIDERED:

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EXAMINER: INITIAL IF REFERENCE CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED. INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.

INFORMATION DISCLOSURE STATEMENT — PTO-1449 (MODIFIED)

| | | | |
|---|---|-------------------|---|
| Form PTO-1449 (modified) | Atty. Docket No. 102-0090US-C | Serial No. unk | 2 |
| List of Patents and Publications for Applicant's INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary) | Inventor/Applicant: Christophe Pierrat et al./ Micron Technology, Inc. | | |
| | Title: PROCESS FOR DETECTING DEFECTS IN PHOTOMASKS | | |
| | Filing Date: herewith | Group: | |

U.S. Patent Documents

| Exam. Init. | Ref. Des. | Document Number | Date | Name | Class | Sub Class | Filing Date of App. |
|-------------|-----------|-----------------|----------|----------------|-------|-----------|---------------------|
| BL | A23 | 5,125,040 | 6-23-92 | Matsui | / | / | 9-24-90 |
| BL | A24 | 5,862,058 | 1-19-99 | Samuels et al. | / | / | 5-16-96 |
| BL | A25 | 5,849,440 | 12-15-98 | Lucas et al. | / | / | 1-29-97 |

Foreign Patent Documents

| Exam. Init. | Ref. Des. | Document Number | Publication Date | Country | Class | Sub Class | Translation Yes/No |
|-------------|-----------|-----------------|------------------|---------|-------|-----------|--------------------|
| BL | B1 | 0485274A2 | 5-13-92 | Europe | / | / | Yes |
| BL | B2 | 138639 | Apr. 1995 | Europe | / | / | Yes |

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| Exam. Init. | Ref. Des. | Citation |
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| BL | C1 | S. Takeuchi, et al., "Advanced 5x reticle inspection technologies for ULSI devices," Integrated Circuit Metrology, Inspection, and Process Control IV, Vol. 1261, 1990, pp. 195-205. |
| BL | C2 | Splat v5.0 Users' Guide (U. California Berkeley) (Jan. 19, 1995). |
| BL | C3 | S. Wolf et al., "Silicon Processing," Vol. 1, Lattice Press, pg. 483-485. |

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